

Multiscale-Multiphysics modeling of nanostructured devices: The TiberCAD project.

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TIBERLAB



University of “Tor Vergata”



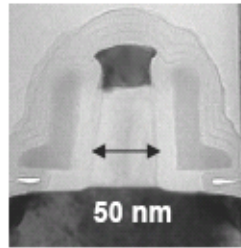
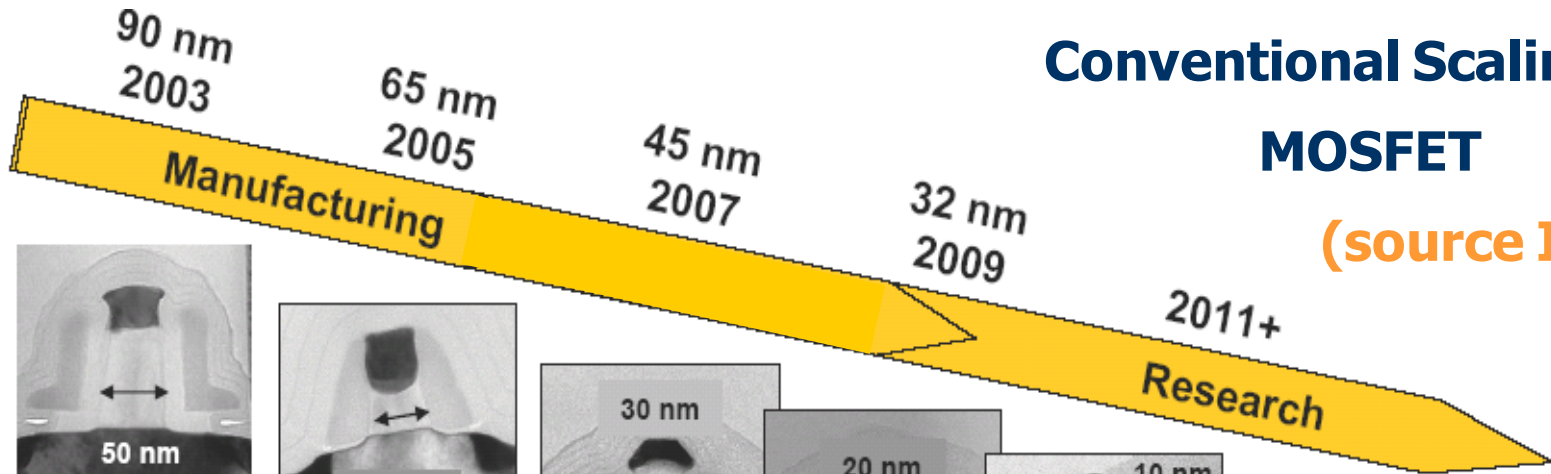
The Moore law

2 in 1.5 years

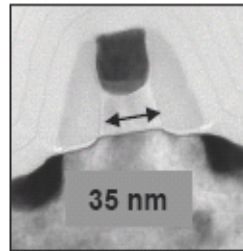
Downscaling example

Conventional Scaling MOSFET

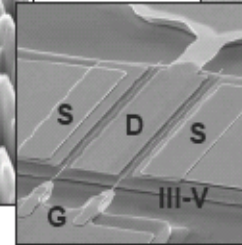
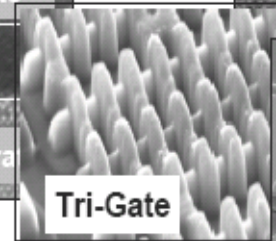
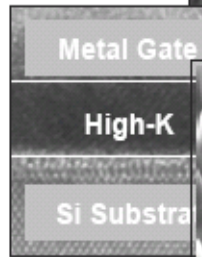
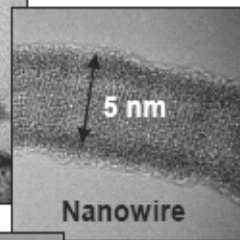
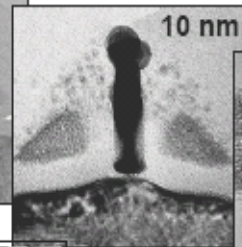
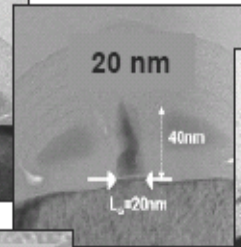
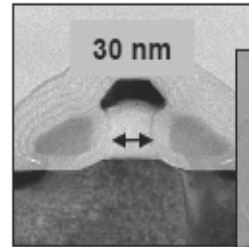
(source INTEL)



SiGe S/D
Strained Silicon



SiGe S/D
Strained Silicon



More Non-Silicon Elements Introduced



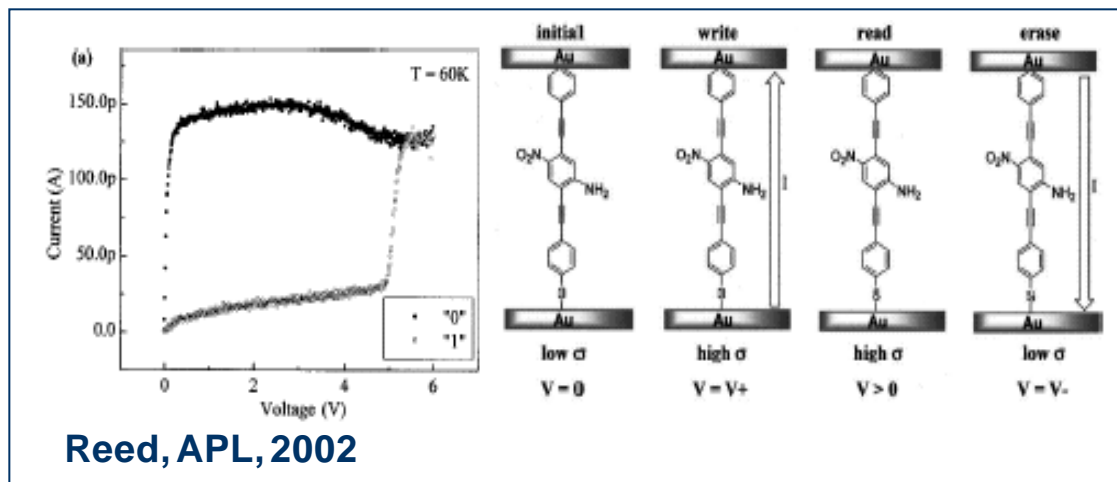
Manufacturing cost increases

Beyond MOS: molecular electronics

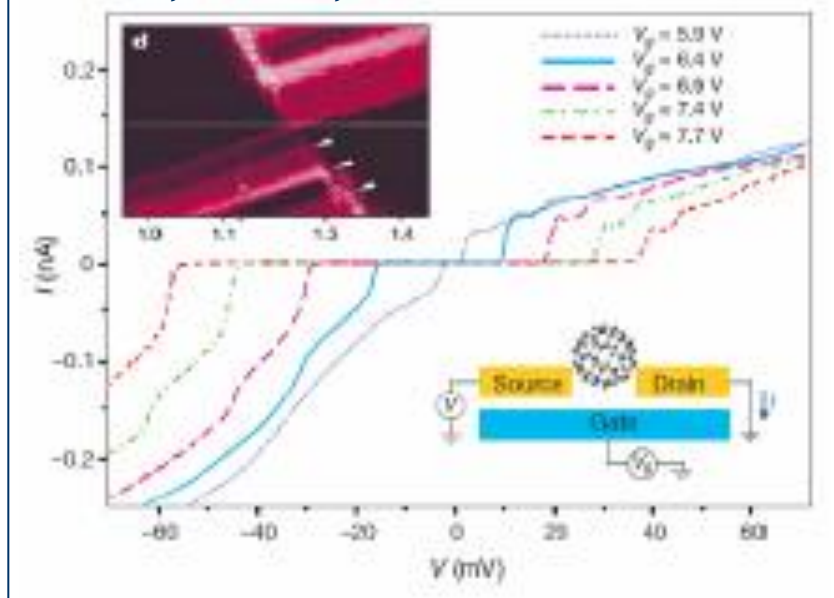
Electron transport across molecules

Structural modification

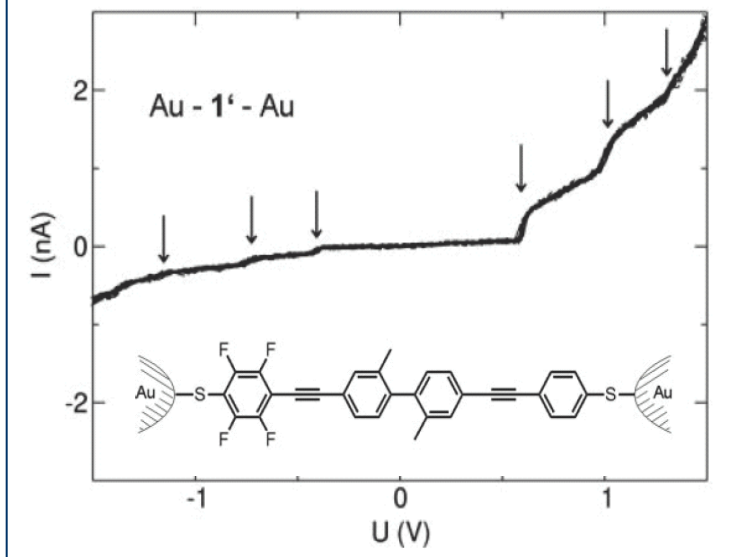
Coulomb blockade



H. Park, Science, 2003



Heiko, PNAS, 2005





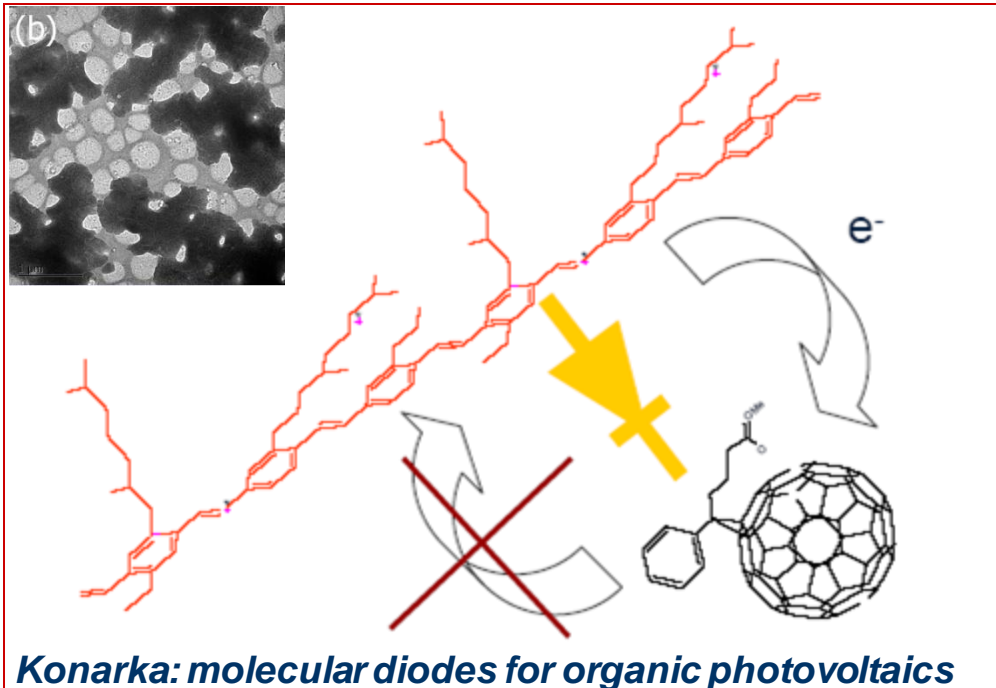
The Obama law

777 in 5 years

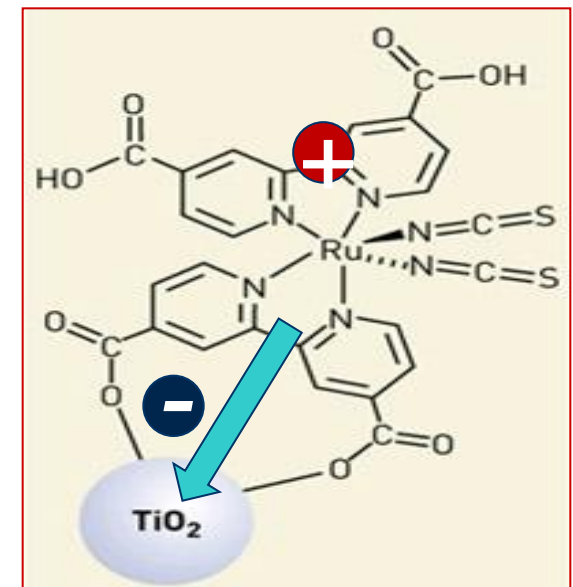
Department of Energy will invest \$777 million in Energy Frontier Research Centers (EFRCs) over the next five years

Nanodevices for Renewable Energy

*Polimeric Bulk heterojunction solar cell
(KONARKA, USA)*

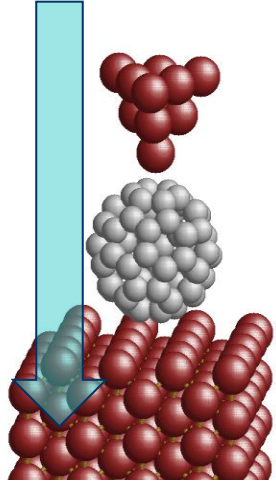


*Dye Solar Cell
(CHOSE, Rome, Italy)*



Atomistic methods

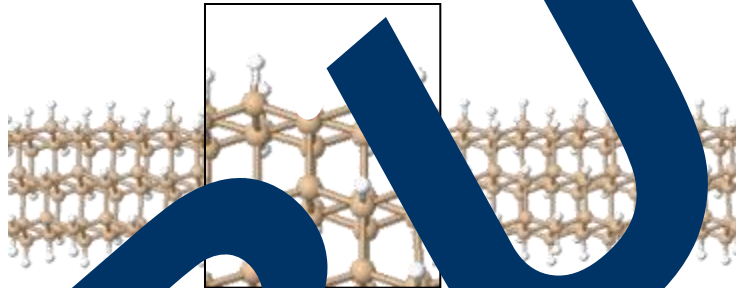
At the nanoscale “every atom matters!” (M. Stettler)



Density Functional TB + NEGF + scattering
[PRL 100, 136801 (2008)]

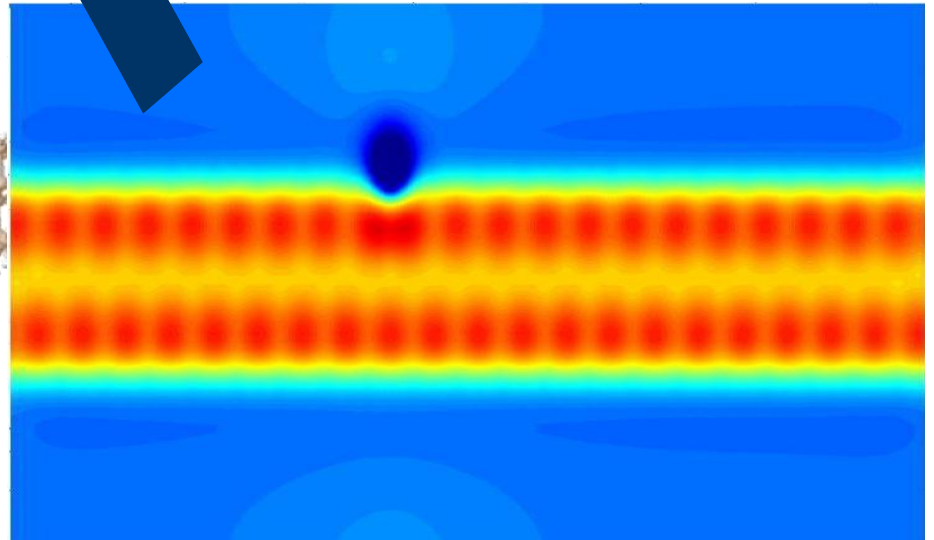
Power dissipated by the C60 molecule is 10 nW

Power calculation $I \times V = 10 \mu\text{W}!!!!$



massive $10 \mu\text{W}$ with one

- dangling bond
- Or massive dangling bond



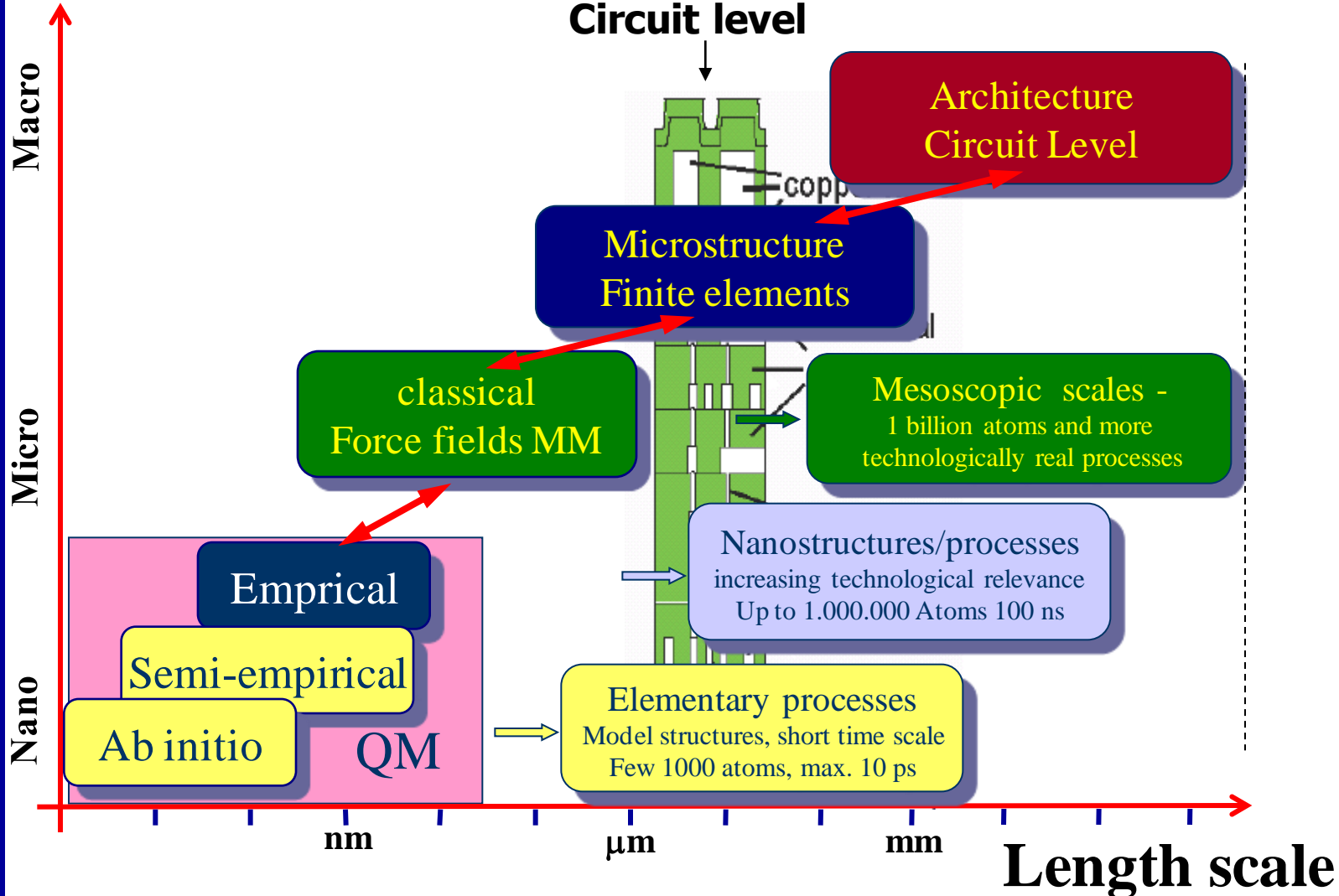
In a real device also micro and macro scale should be considered

- *Number of atoms cannot grow to much in simulations*
- *Device should be accessible from a macro scale*
- *micro/macro scale details are as important as nanoscale features
(temperature distribution, electrostatics, strain, air gap, etc.)*
- *20 years of experience with Drift-diffusion matters !*

The multiscale problem

Typical Pentium 4 MOSFET section

Circuit level

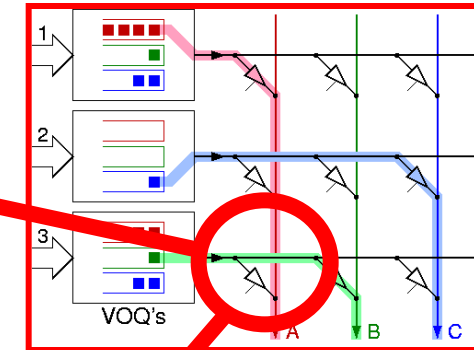
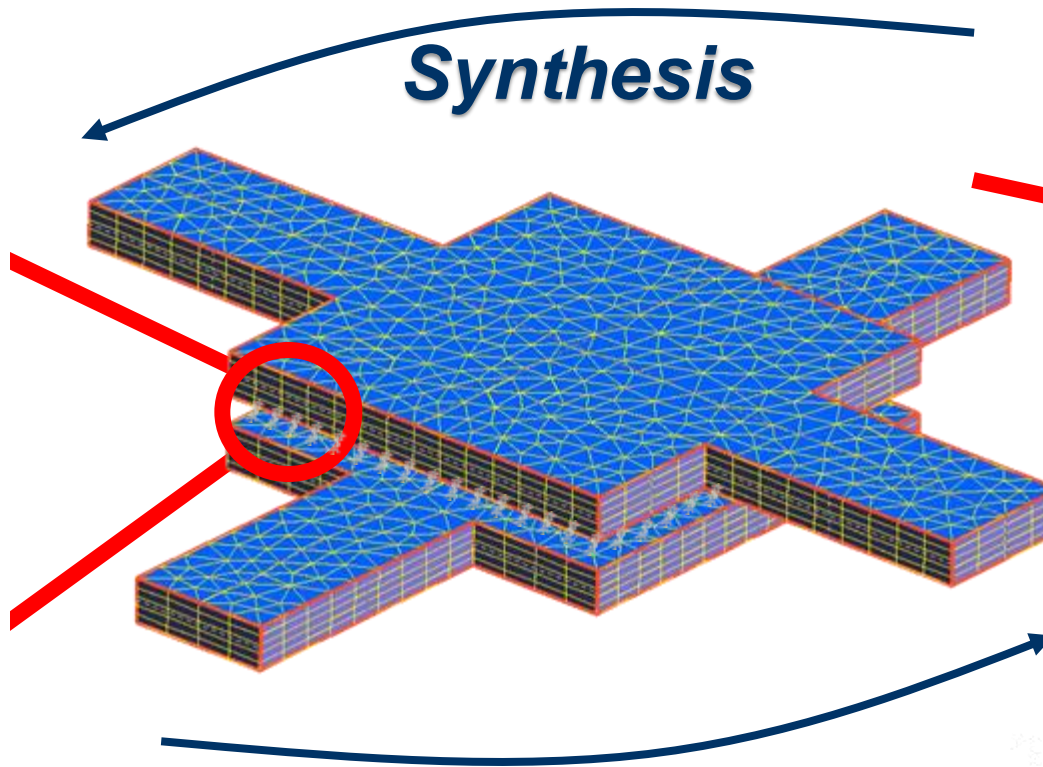
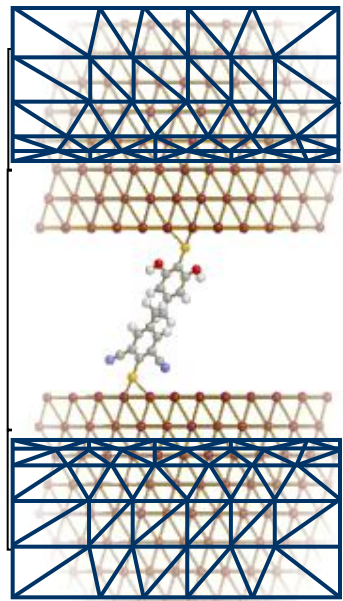


Multiscale simulation approaches

Quantum description

Macro-Microscopic description
(Strain, Drift-Diffusion, Heat, etc)

Circuit simulation

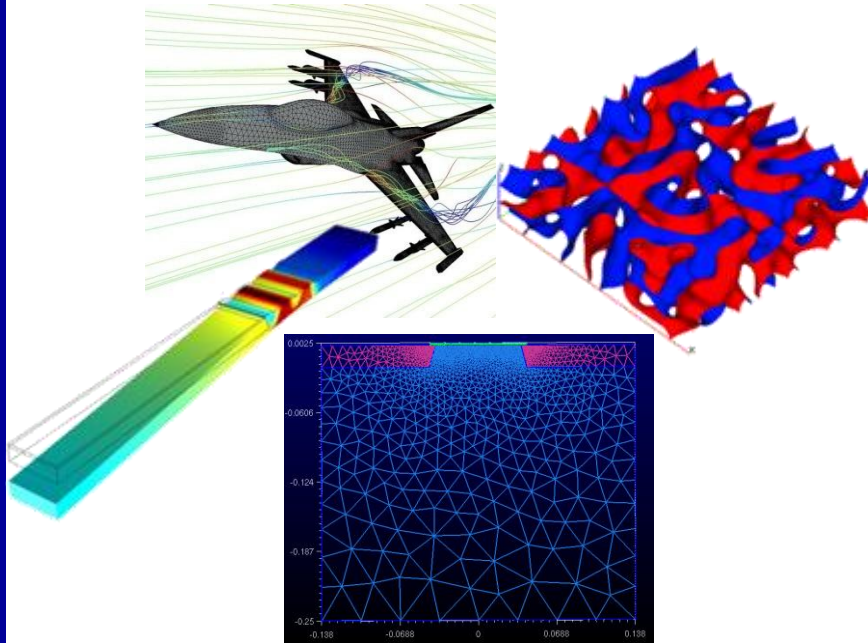


Analysis



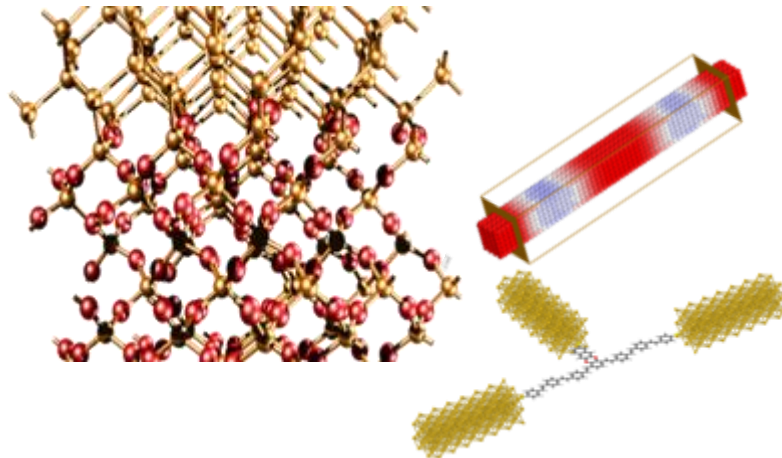
www.tibercad.org

Multiscale components



Finite Element Method

- FEM is the method in engineering problems (deformation/strain, heat, Maxwell, etc. etc.)
- Drift-diffusion (DD) like schemes have been solved with box integration methods.
- DD-FEM have been heavily developed in the last 20 years in the Math community (**Hecht, Marrocco, Brezzi, Sacco, Chen**)
- many FEM library in GPL



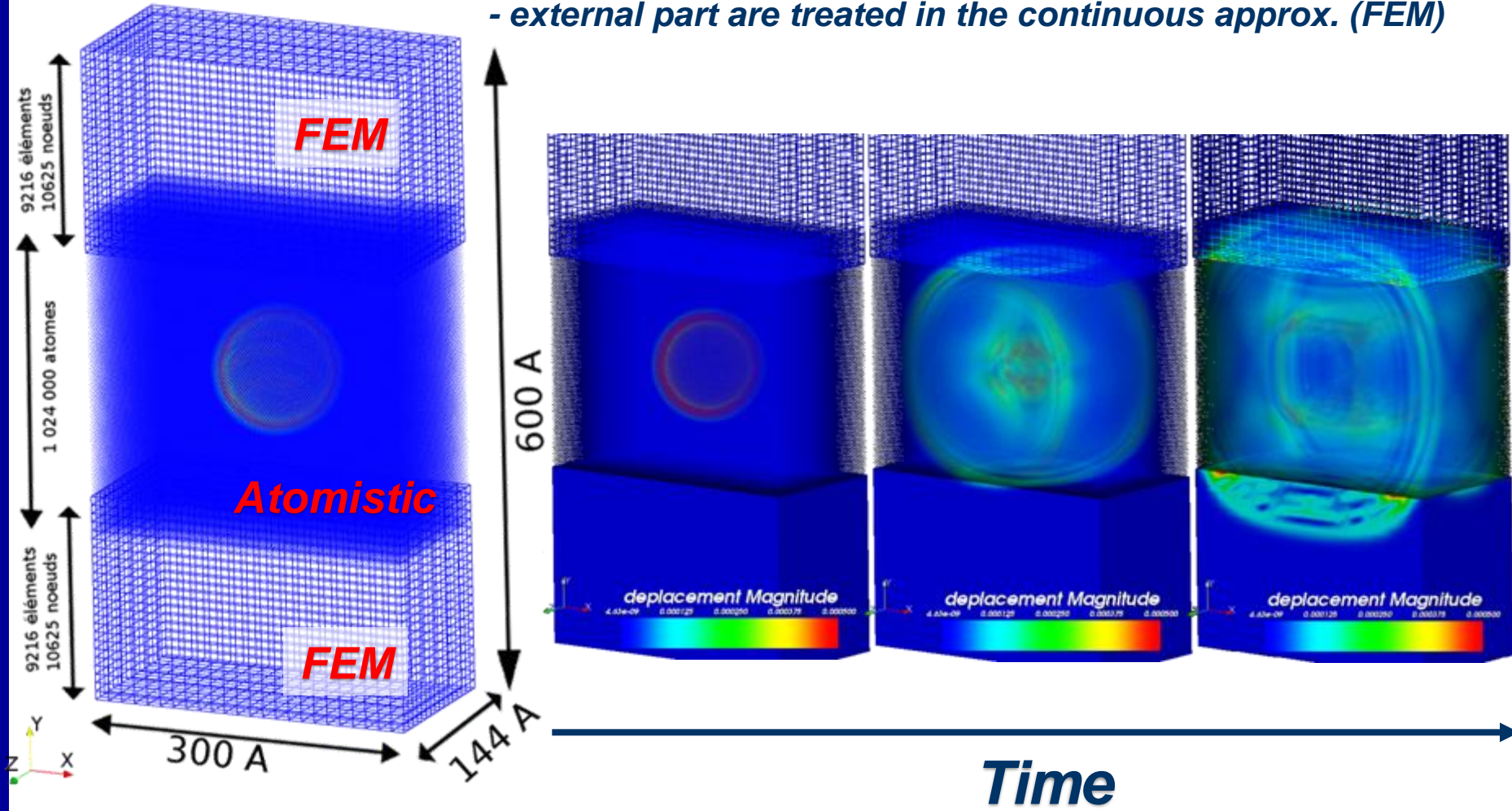
Atomistic local basis

- Localized basis approach are very well suited for device simulations
- Empirical approaches (ETB)
- Approximate DFT (DFTB)
- Full DFT (Siesta, DMOL, etc.)

Multiscale methods in material science

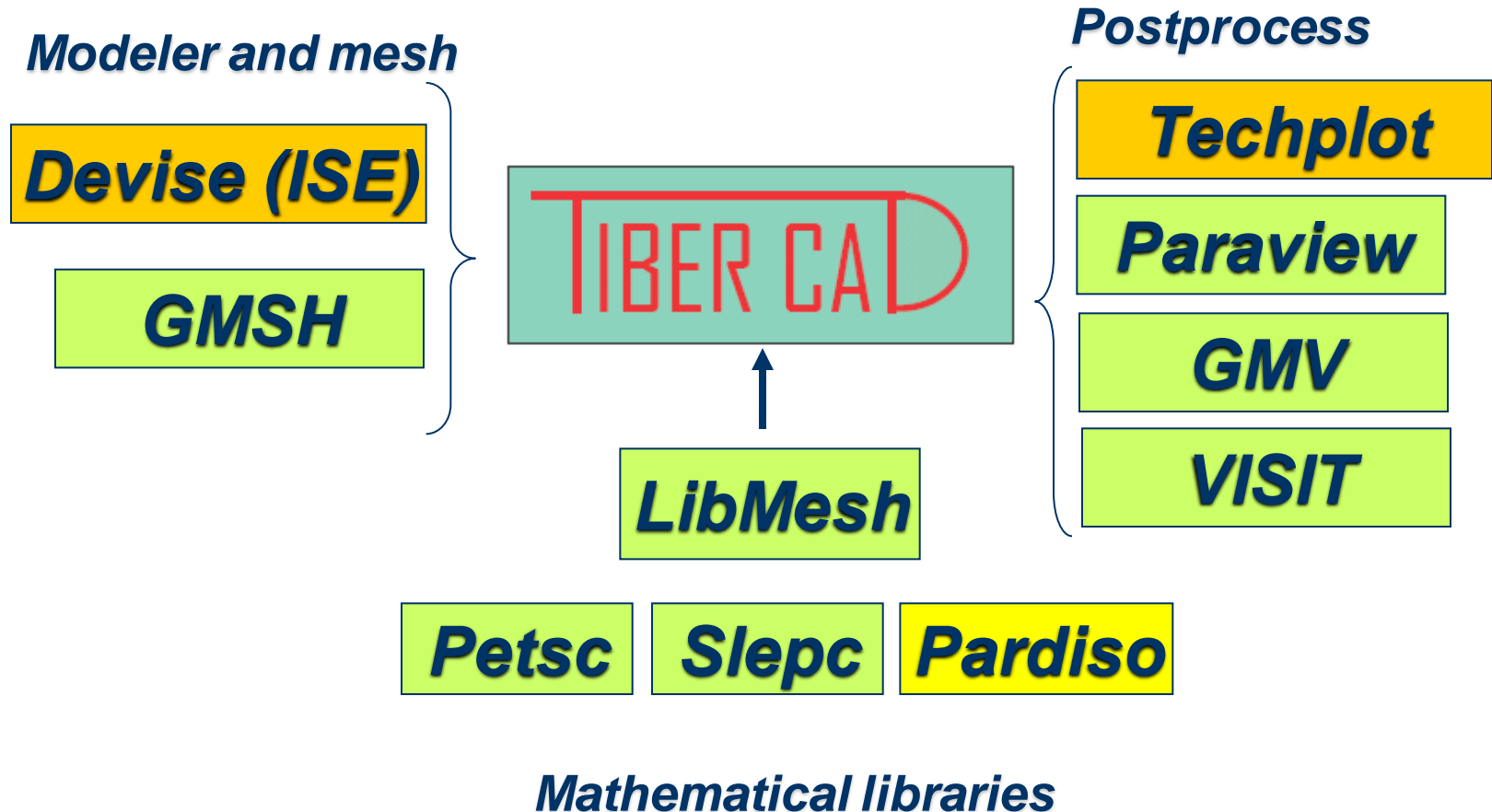
Propagation of a shock wave in a crystal

- central region is treated at the atomistic level (MM)
- external part are treated in the continuous approx. (FEM)



Courtesy of G. Anciaux

TiberCAD structure



Development is done in C++ in Linux, porting to other UNIX-like environments and Windows has been achieved

TiberCAD 1.0 is freely downloadable at www.tibercad.org

- Mechanical deformation with any kind of constrain
- Semiconductor Strain including piezoelectric effect
- Drift-Diffusion transport of electrons / holes / excitons / Ions (+ Poisson)
- Heat transport
- Quantum mechanics based with **k·p** envelope function approximation
- Atomistic description via Density functional Theory and Empirical Tight-Binding (sp³d⁵s*, or any other basis)
- *NEGF(developed but not yet integrated)*
- *Classical molecular mechanics (in progress)*
- *Maxwell solver (in progress)*

TiberCAD features

- *1D, 2D, 3D and cylindrical symmetry*
- *Adaptive meshes*
- *Written to run parallel (but not yet tested)*
- *Input parser with a syntax similar to commercial TCAD*
- *Interfaces with some commercial TCAD*
- *Possibility to link user defined models*



Numerical Implementation

- All PDE based models are discretized by means of the finite element method (FEM) by using Fermi level as variables !
(in contrast to conventional approaches which uses box integration and densities as variables)
- The linearized equations are discretized using standard Galerkin FEM, using a piecewise linear basis (hat functions)
- Jacobian is asymmetric and ill-conditioned as the diffusion coefficients in the linearized continuity equations are proportional to the particle densities.
- The conditioning is improved by a proper diagonal scaling.
- A M-matrix form of the Jacobian is looked for (proper stabilization procedure)
- The linear system is solved by means of iterative solvers (bi-conjugate gradient with ILU preconditioning), using the open-source library PETSc
- Numeric Gauss integration for integrals

Physical Models: strain (linear)

define shape

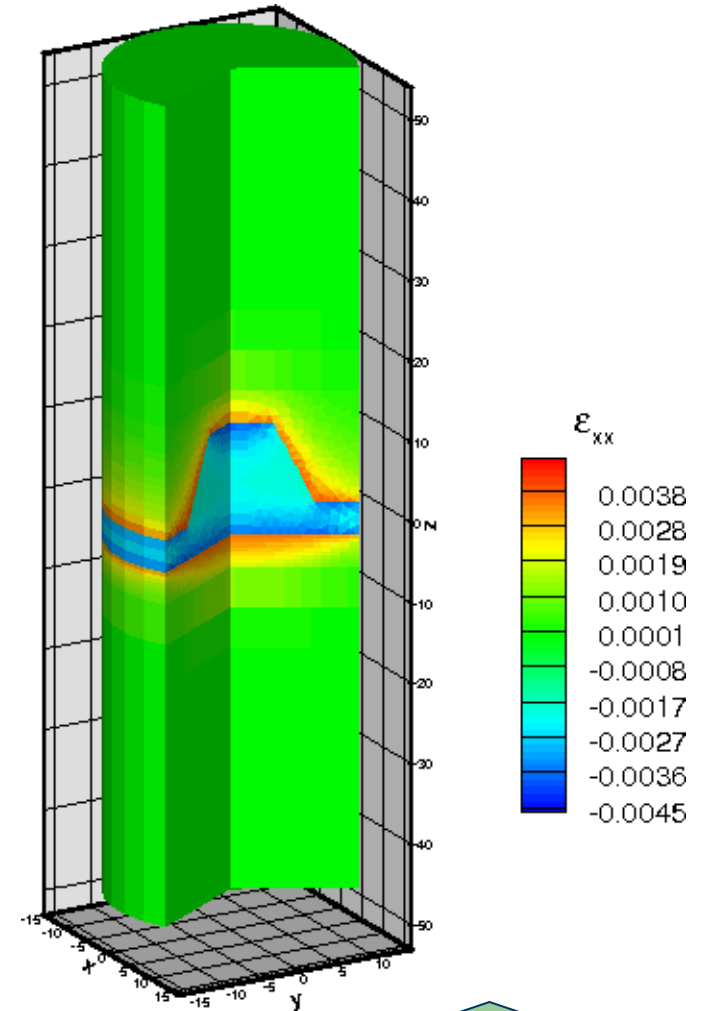
$$\varepsilon_{ij}^0 = \delta_{ij} \frac{a_i^S - a_i}{a_i}$$

Minimization
of the elastic
energy

$$\frac{\partial}{\partial x_i} \left(C_{ijkl}(\mathbf{r}) \left(\frac{\partial u_k}{\partial x_l} + \varepsilon_{kl}^n(\mathbf{r}) \right) \right) = 0$$

Strain tensor

$$\varepsilon_{ij}^n = \frac{1}{2} \left(\frac{\partial u_i}{\partial x_j} + \frac{\partial u_j}{\partial x_i} \right)$$

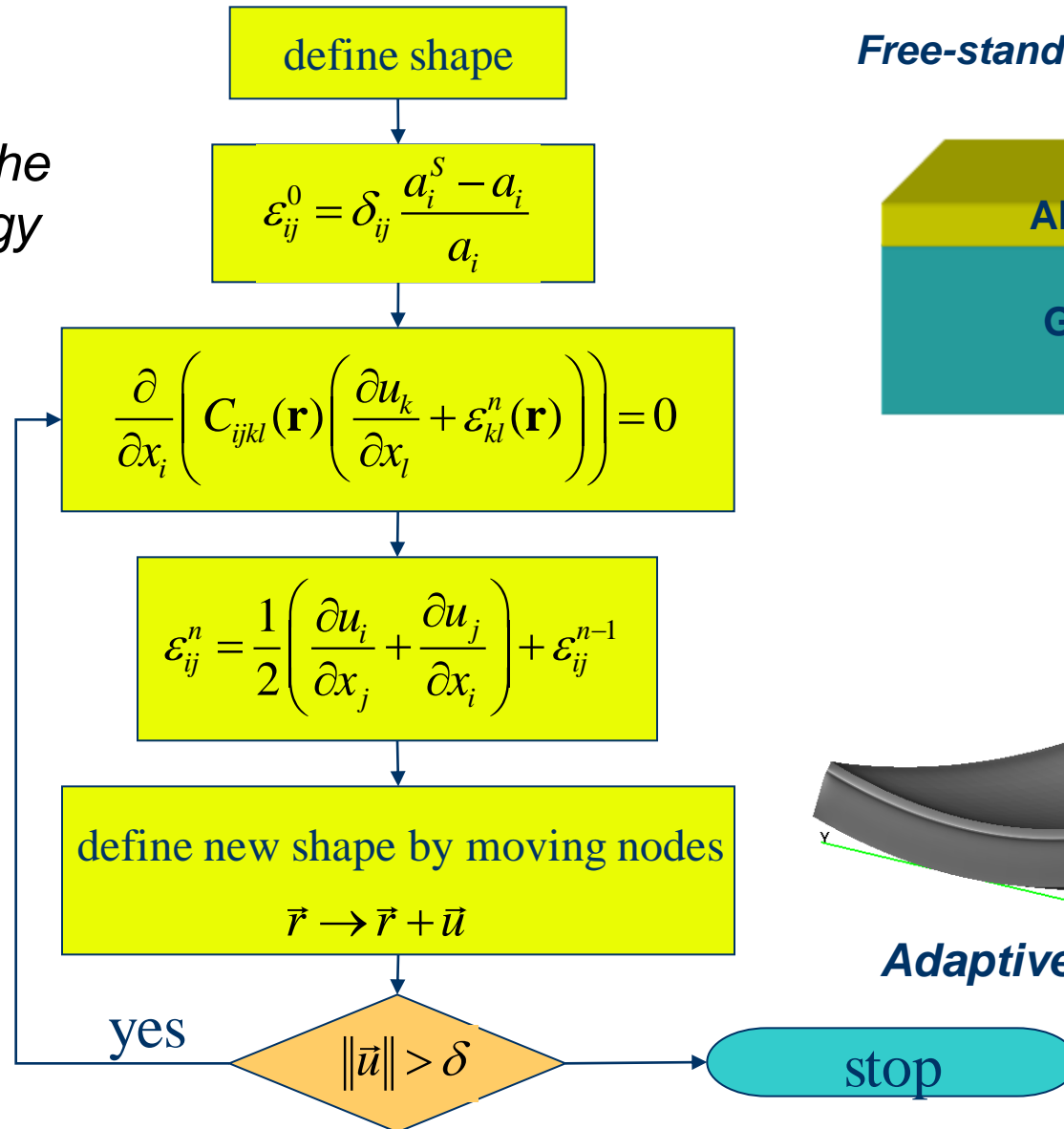


GaN dot in a/AlGaIn
nanocolumns

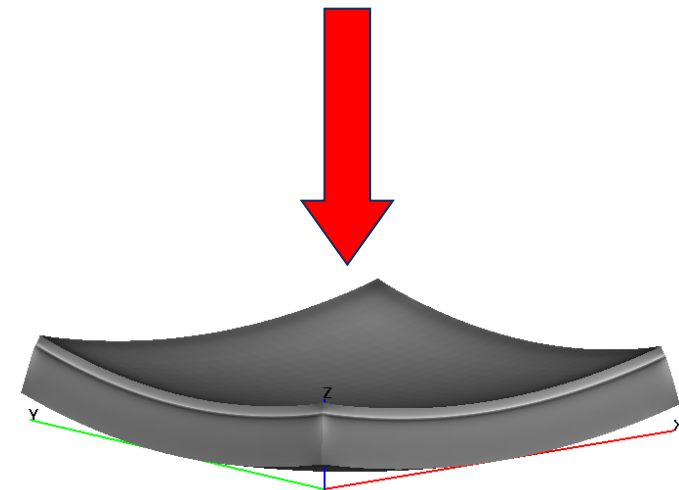
Physical Models: strain (non-linear)

Povolotskyi-Di Carlo, JAP 100, 063514 (2006)

Minimizing the elastic energy with self-consistency cycles

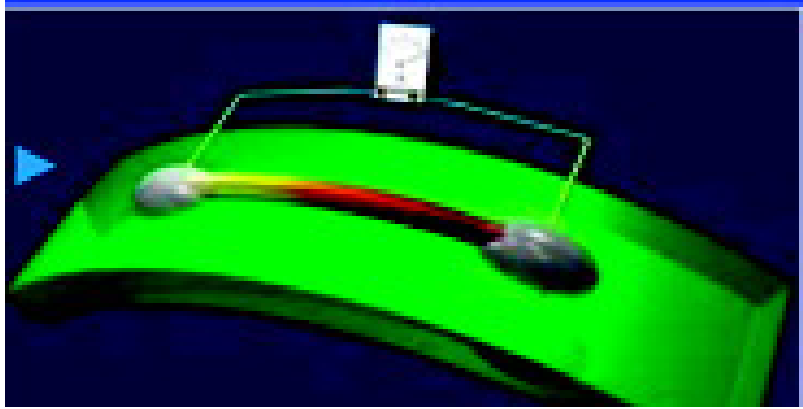


Free-standing AlGaIn/GaN



Adaptive grid are used

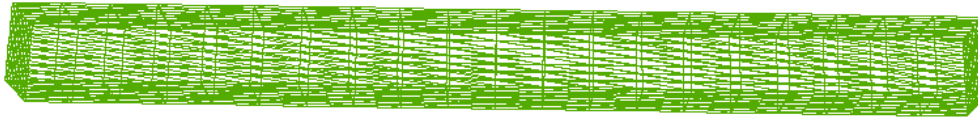
ZnO₂ Wang nanogenerator



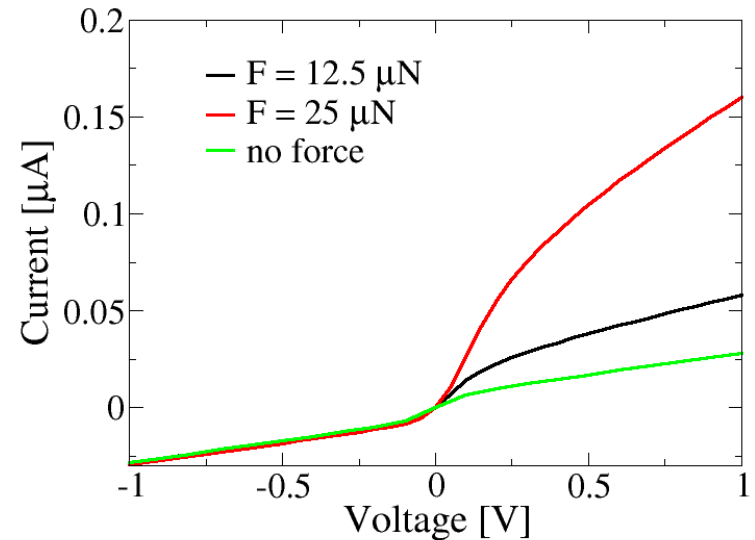
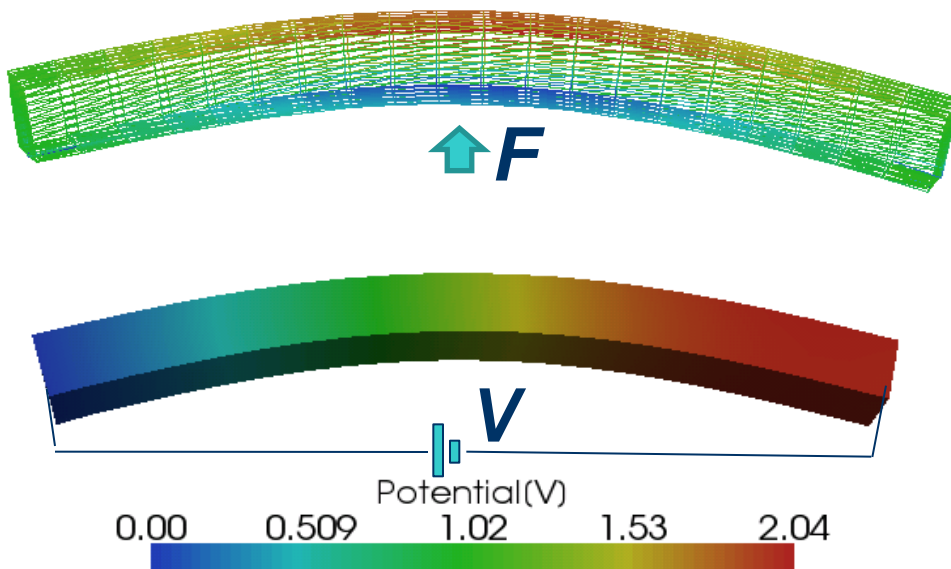
Zhong Lin Wang investigated nanogenerators for converting mechanical energy into electricity.

Zhong Lin Wang. *Adv. Funct. Mater.*, 2008.18, 3553-3567

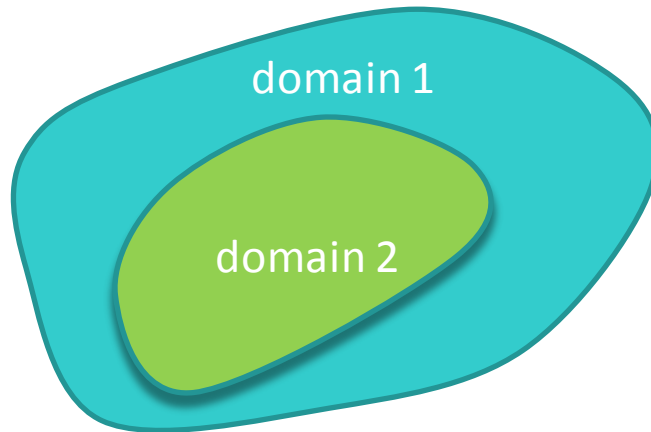
Rusen Yang, et al. *Nano Letters*, 9 (2009) 3, 1201-1205.



Jun Zhou et al, *Nano Letters*. (2008)



OVERLAP METHOD



- the domains are overlapped
- each model computes physical quantities that act as parameters to the other models.

BRIDGE METHOD



- the domains are contiguous and linked through $n-1$ dimensional regions.
- each domain provides boundary conditions to adjacent domains.

Multiscale simulations: OVERLAP method

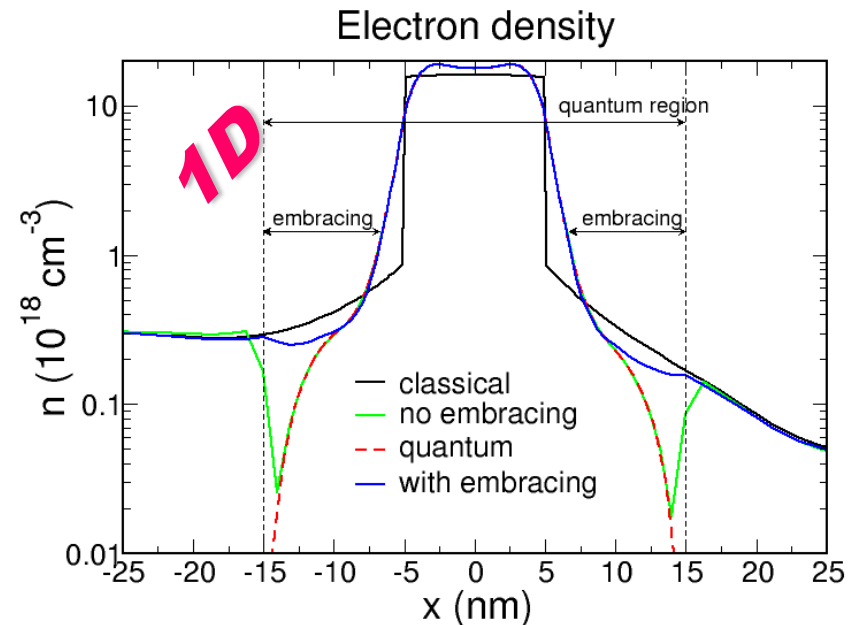
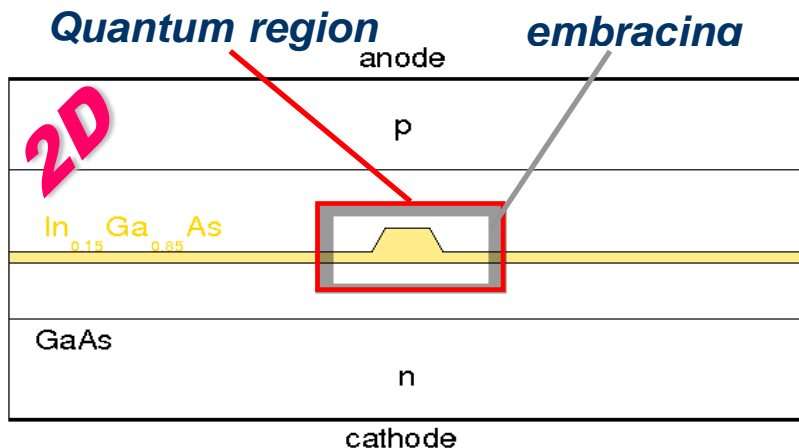


Classical/quantum densities: Embracing

For a smooth transition between classical and quantum density we introduce an automatically generated embracing region where the densities get mixed:

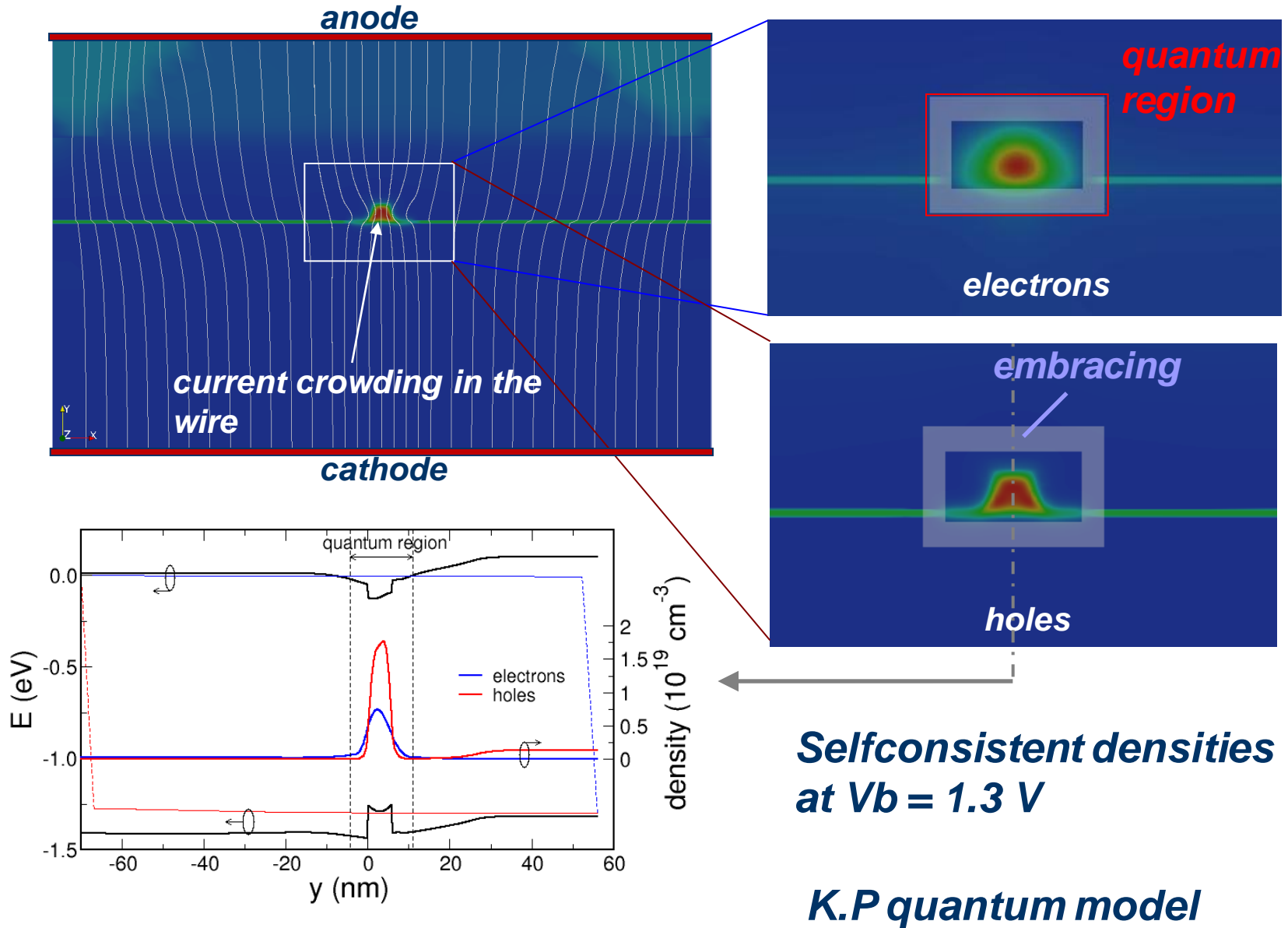
$$n(x) = \lambda(x) \cdot n_Q(x) + [1 - \lambda(x)] \cdot n_{cl}(x)$$

where $\lambda(x)$ is the solution of a Laplace equation in the embracing region.



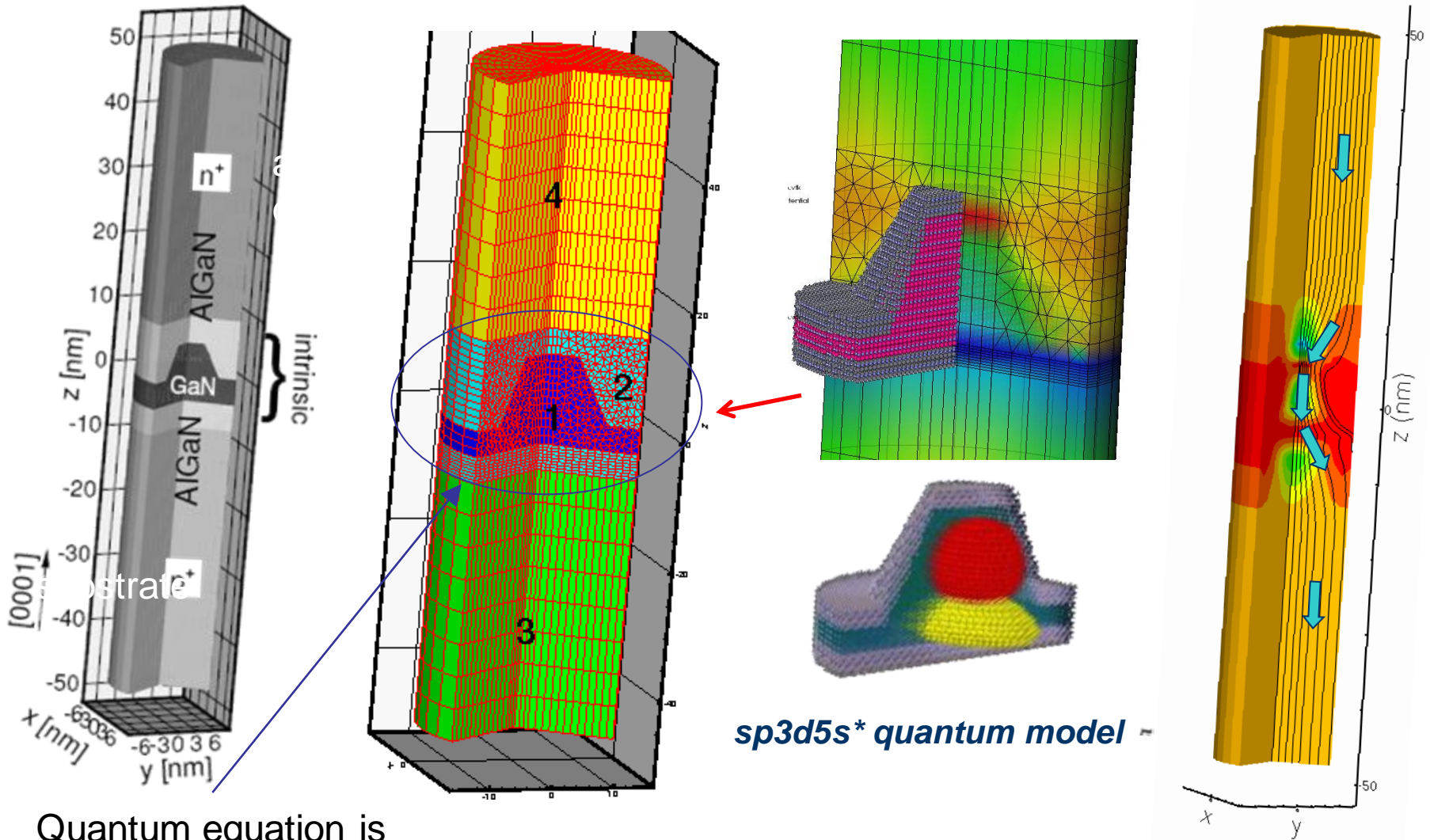
K.P quantum model

InGaAs Quantum wire



GaN/AlGaN Quantum Dot

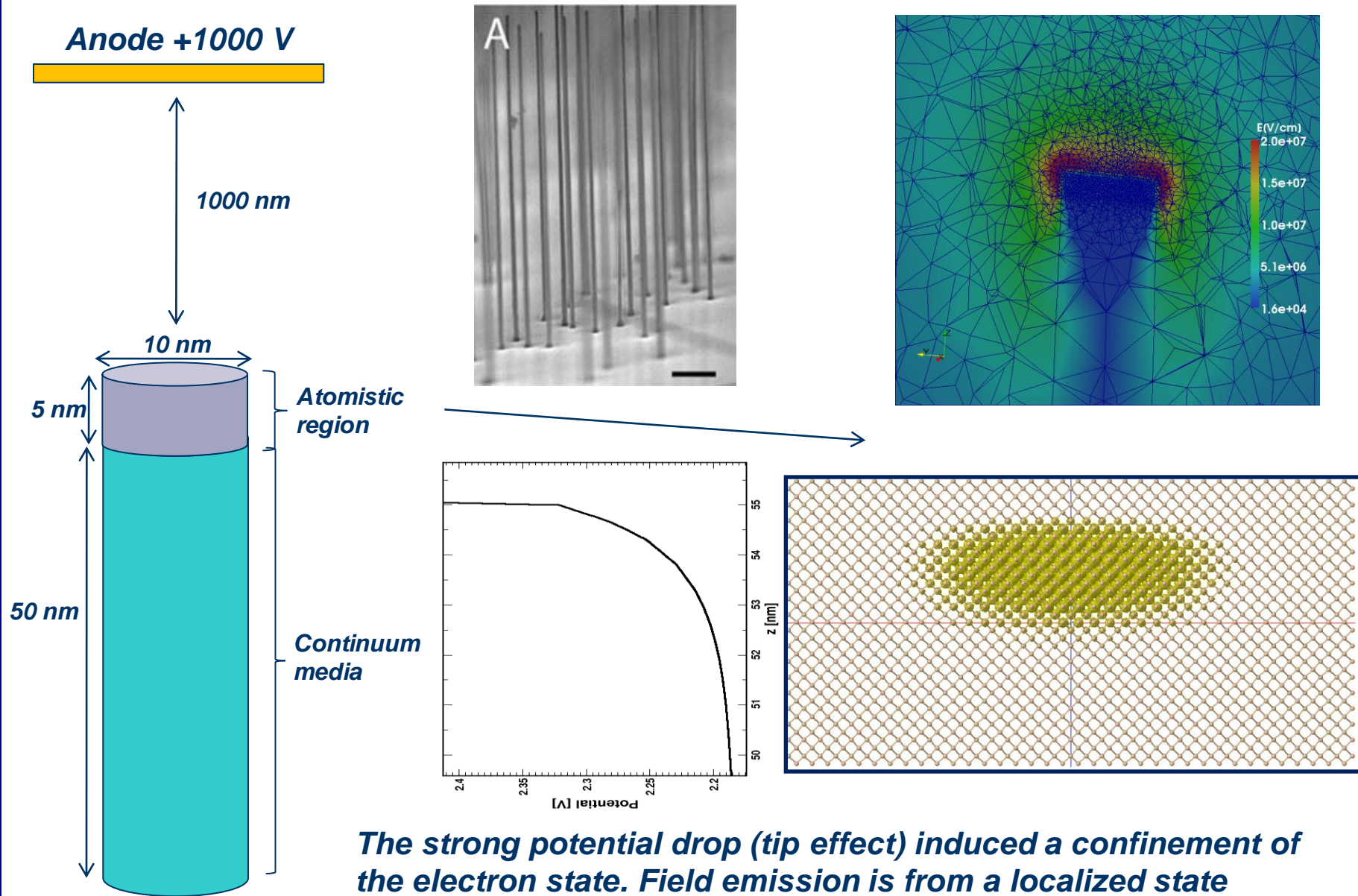
Macroscopic \leftrightarrow Atomistic projection of potentials and densities



Quantum equation is solved only here (1 + 2)

Details in the G. Penazzi talk

SiNanowire for field emission

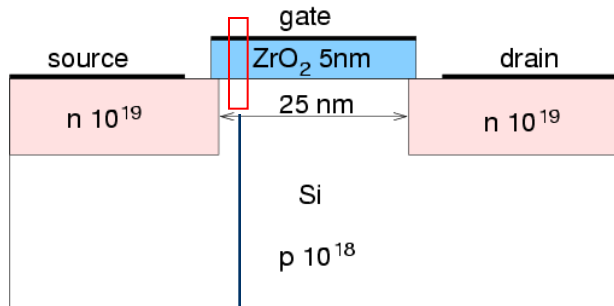


Multiscale simulations: BRIDGE method

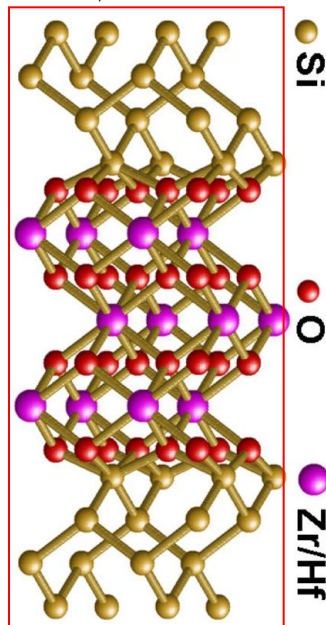
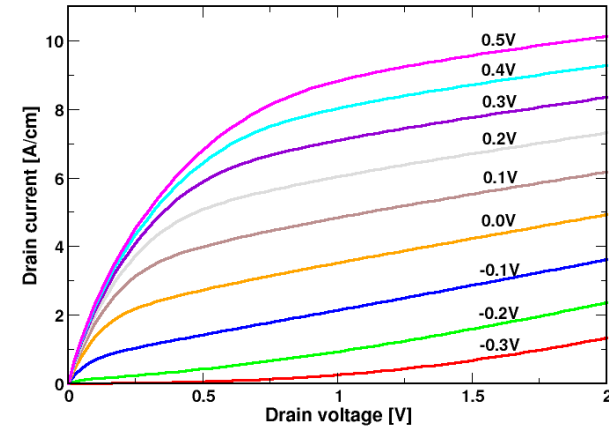


Multiscale simulation example: MOSFET

Drift-diffusion simulation of a 25 nm MOSFET with SiO_2 and high- κ oxide, including gate-tunneling



Classical Drift-Diffusion simulations



Tunneling current calculation based on an atomistic semi-empirical tight-binding description.

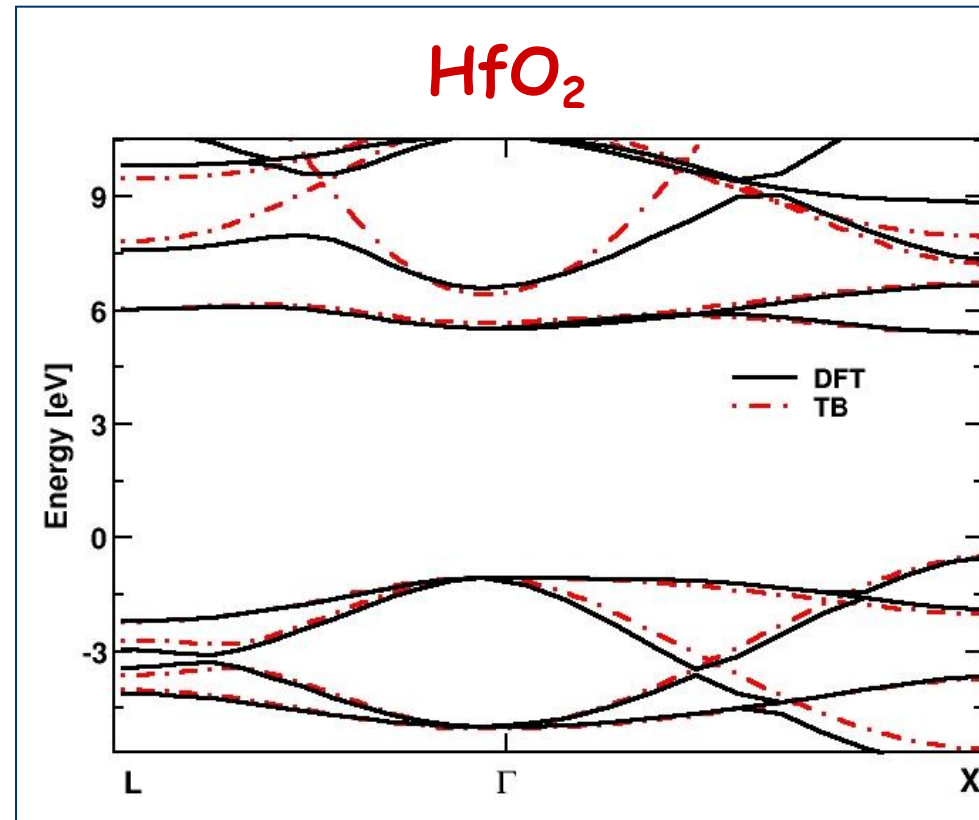
How can we merge these two scales?

SiO₂, HfO₂ and ZrO₂ cubic crystalline forms

- DFT total energy calculation
- optimization of lattice parameters
- energy band dispersions

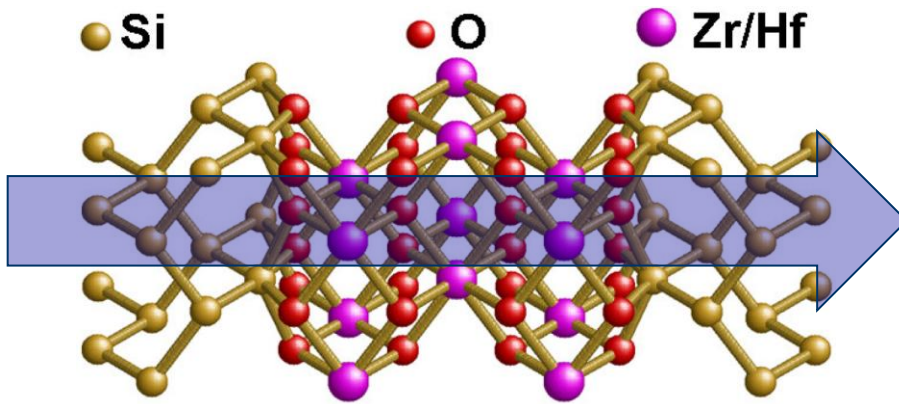
■ Effective mass approach cannot be easily applied and a full band calculation is required

■ Tight Binding parameterization of SiO₂, HfO₂ and ZrO₂ has been determined to fit DFT calculations and experimental band gaps. A sp³s*d⁵ model has been used

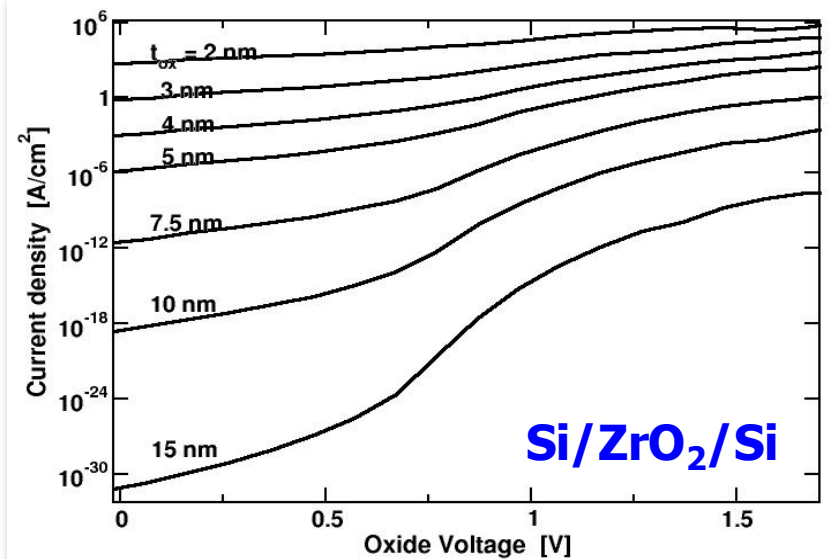
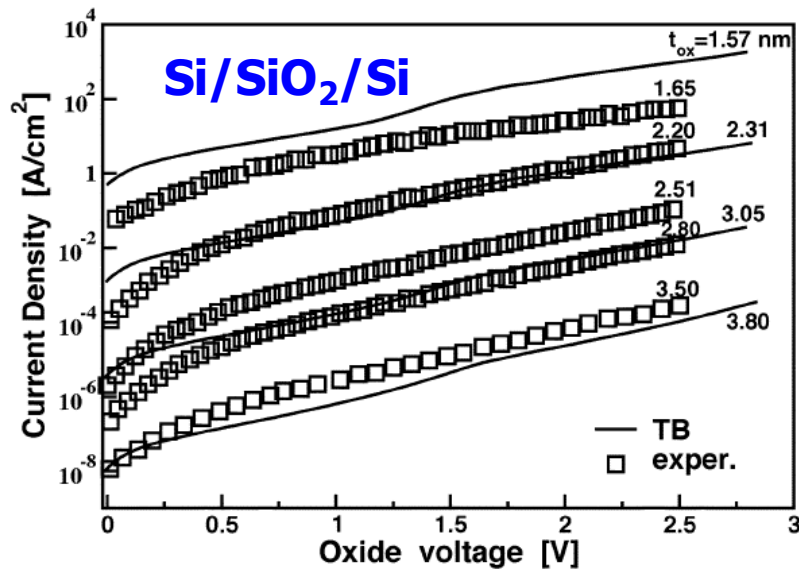
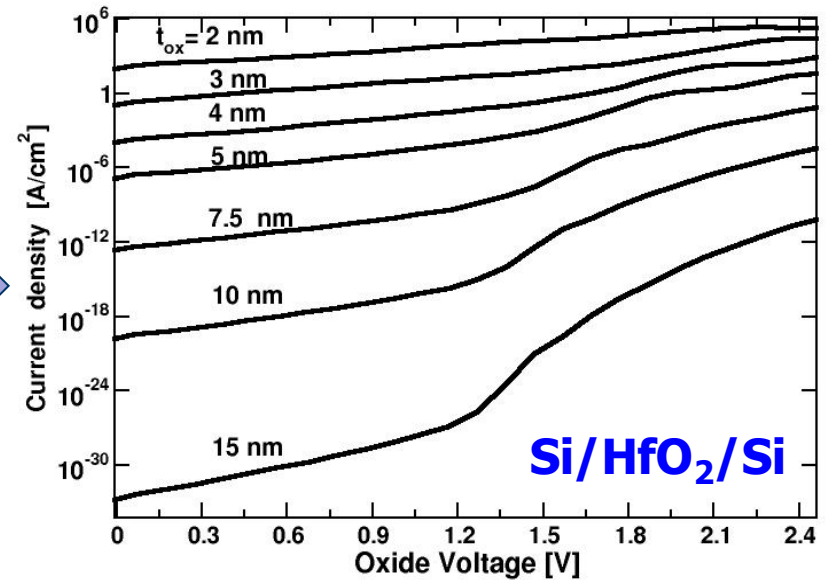


- Calculation of tunneling properties with transfer matrix method in ETB framework

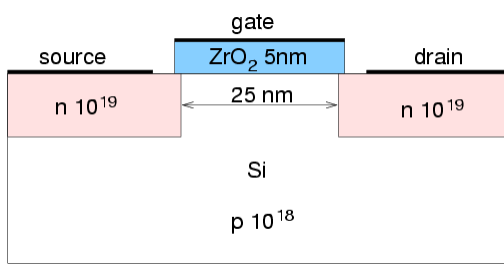
Atomistic description of tunneling current in MOS



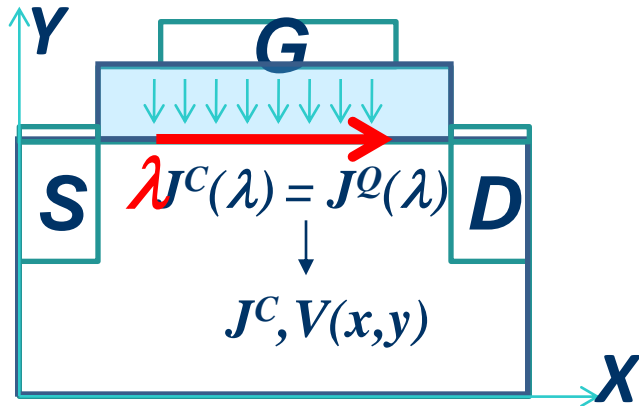
Sacconi et al IEEE TED 2004 and 2007



Bridge method: flux continuity



$$J_y^C(\lambda) = 0$$



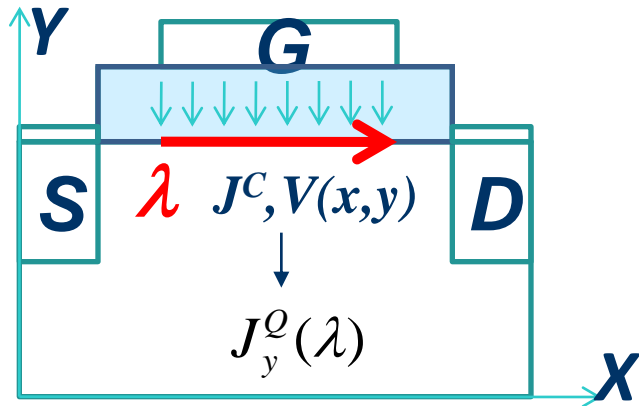
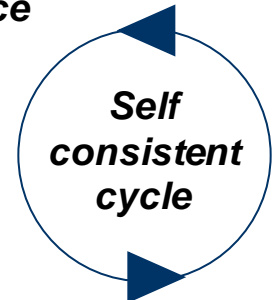
$$\mathbf{J}^C = \mu_n n \nabla \phi_n$$

$$\nabla \cdot \mathbf{J}^C = G - R$$

$$\nabla \cdot (\epsilon \nabla V) = -\rho$$

Poisson-Drift-Diffusion is solved in the whole device

$$J_y^C(\lambda) = J_y^Q(\lambda)$$



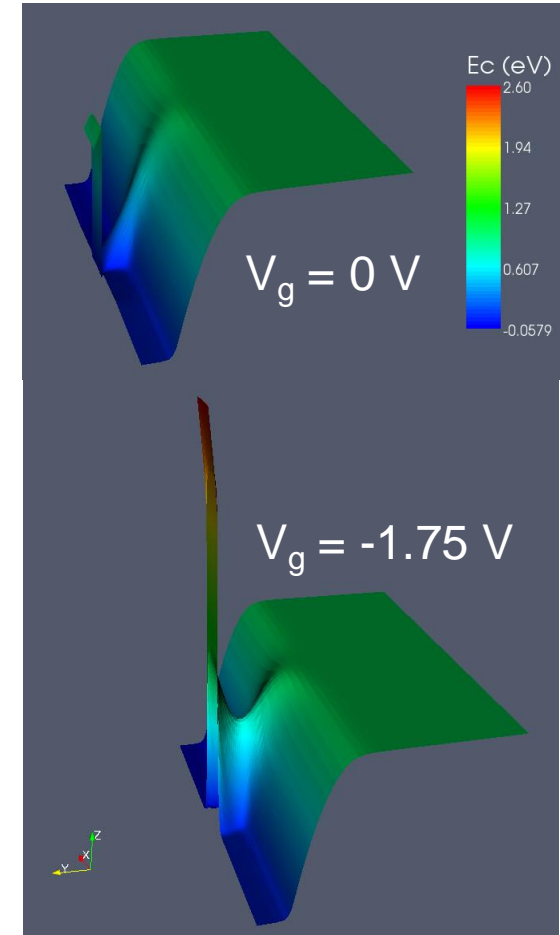
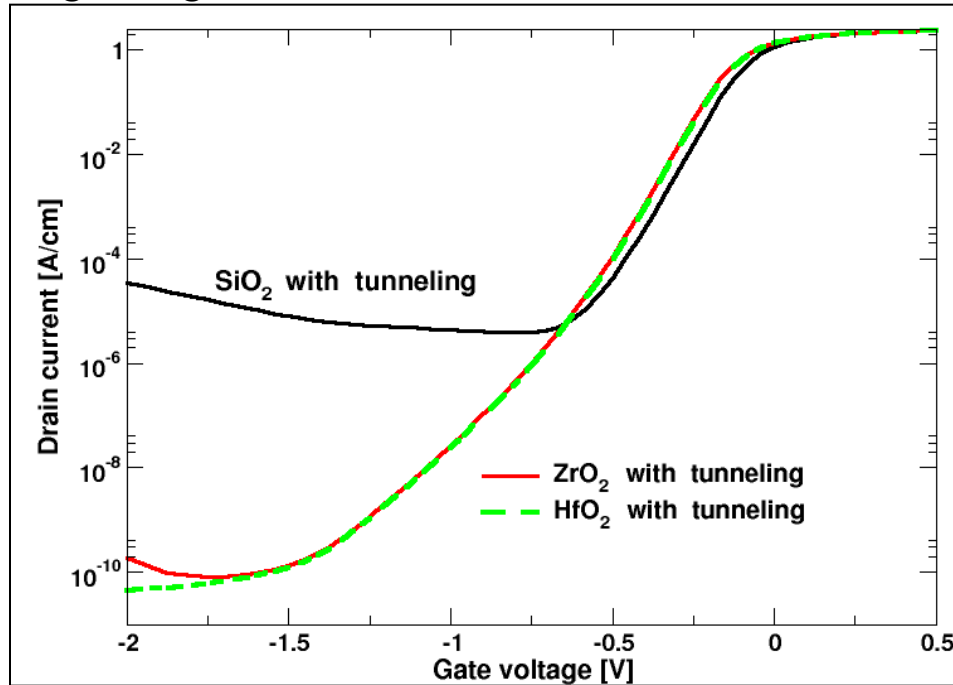
$$V(\lambda)$$

$$J_y^Q(\lambda) = f(V(\lambda) - V_G)$$

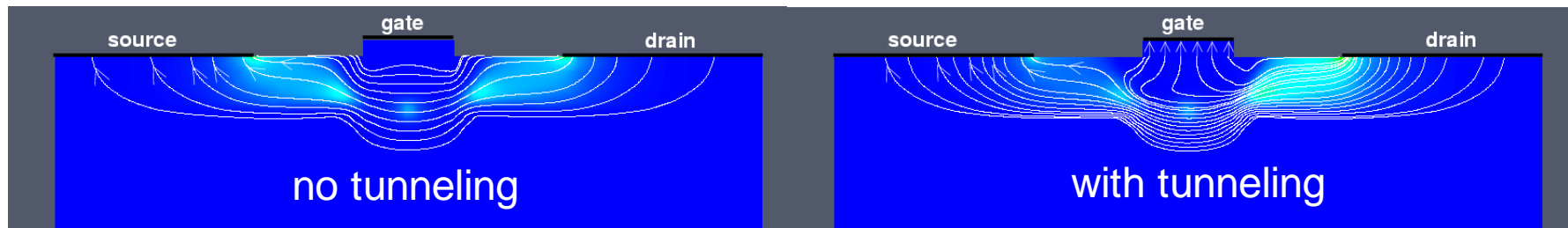
Tunneling current calculated with atomistic tight-binding model is taken as a boundary condition for electron continuity at Si/oxide interface

MOSFET: multiscale simulation

The effect of the oxide tunneling can be seen in the subthreshold characteristic at high negative bias:

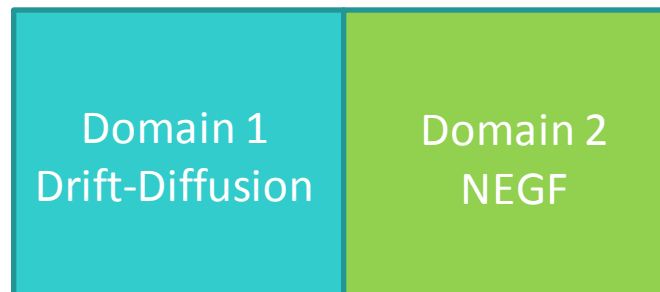


Current flow lines at $V_{ds} = 0.1$ V, $V_g = -1.75$ V:



Conclusions and outlook

- Multiscale/multiphysics is requested in real modern materials and devices where electronics optics chemistry (and biology) are linked together
- TiberCAD in one of the first attempt to answer this request
- Much effort is still needed to arrive at a consistent multiscale integration for transport simulations such as a coupling between NEGF and DD (IWCE14)



Additional details at <http://www.tibercad.org>